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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Art Unit:

In re Applicant:

Ilya Karpov et al.

10/822,361

2814 Examiner: Long Pham

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Serial No.:

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For:

Fabricating Deeper and Shallower Trenches in Semiconductor Structures Assignee: Conf. No. Intel Corporation

Mail Stop AF Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

## REPLY TO FINAL REJECTION

Sir:

In response to the final rejection mailed August 15, 2007, please amend the abovereferenced patent application as follows: